

Photosensitive material for immersion photolithography

ABSTRACT OF THE INVENTION

3 When rays of light converge inside a photosensitive material at angles larger than 70 degrees, one
4 polarization of the light may fail to produce the desired image contrast in conventional exposure
5 media. This invention describes a material which may be applied to a semiconductor wafer
6 surface which ensures that the photosensitive material is exposed principally by light polarized
7 parallel to the semiconductor wafer surface.